Tool ID: 219
Tool Location: 114

Equipment Information Sheet

AJA Ion Mill

Manager: Aaron Windsor 607-254-4831
Backup: Christopher Alpha 607-254-4913

Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.

SAFETY

- No unusual hazards

USAGE RESTRICTIONS

- No buddy restrictions

SCHEDULING/SIGN-UP RESTRICTIONS

Minimum Tool Time: 15 minutes

- -Maximum 4 hour block reservations anytime
- Maximum 12 hours reserved in advance at any time per person
- No consecutive research group reservations
- Users/Groups may use any amount of unreserved time
- Additional individual restrictions may be imposed

MATERIALS COMPATIBILITY CATEGORY

Tool Category 4: Glass and Metal Categories

Allowed	Not Allowed
Tool category 1/1E, 2, and 3 materials	
Silicon Based Substrates and Films	No CNF Class A metals
III/V compound Semiconductors	**No Exposed CNF Group B metals-** ***metals can be buried/covered with staff approval***
Glass Substrates	Cannot be used as an etch stop
PECVD and ALD Films	
Buried Class B Metals with approval	
Organic/Bio Materials prepped w/o Salt Buffers	
Cured organics and baked Photoresist	No High Vapor pressure materials

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

Additional Material Restrictions and Exceptions

- Samples up to 6 diameter.
- Check with machine manager before etching samples with non-standard materials.
- No Cadmium or Zinc films and substrate materials!

Last Updated: 03/24/2021